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11/26/01

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Yasumasa KAWABE, et al

Appln. No.: 09/295,329

Confirmation No.: Not Assigned

Group Art Unit: 1752

Filed: April 21, 1999

Examiner: Y. Clarke

For: POSITIVE PHOTSENSITIVE RESIN COMPOSITION

AMENDMENT UNDER 37 C.F.R. § 1.311

Commissioner for Patents  
Washington, D.C. 20231

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NOV 21 2001

TC 1700

Sir:

This Amendment is submitted in response to the Office Action dated May 17, 2001. A Petition for a three month extension of time is being concurrently filed, making a response due on or before November 19, 2001 (November 17, 2001 being a Saturday). Please amend the above-identified application as follows:

IN THE CLAIMS:

Please add the following new claims:

B  
Sub  
C1

Claim 23 (new). The positive photosensitive resin composition as claimed in claim 1, wherein said polymer which has alicyclic hydrocarbon skeletons and decomposes under the action of an acid to become alkali soluble contains a repeating unit selected from the group consisting of repeating units having the structural formulas (b-1) to (b-8):